3.46 PHOTONIC MATERIALS AND DEVICES

Lecture 10: LEDs and Optical Amplifiers

Lecture

Notes

References: B. Saleh, M. Teich, <u>Photonics</u>, (John-Wiley), Chapters 15-16.

This lecture will review how electrons and holes recombine in semiconductors and generate photons. The study of light emission in materials is a key factor for the understanding of optoelectronic devices such as LEDs, Optical Amplifiers and Lasers.

$$Photon \ flux: \ \ \varphi_v = I \frac{1}{E_g} = \frac{P}{A} \frac{1}{E_g}$$

I = optical power density

P = optical power

A = beam area

Non-equilibrium

R = non thermal generation rate (carrier injection rate)

 G_0 = thermal generation rate

$$\mathbf{n} = \mathbf{n}_0 + \Delta \mathbf{n}$$
$$\mathbf{p} = \mathbf{p}_0 + \Delta \mathbf{p}$$

$$\Delta n = \Delta p$$

$$\Delta n \ll n_0$$
, p_0

Injection carrier rate equation: $\frac{d(\Delta n)}{dt} = R - \frac{\Delta n}{\tau}$

 τ = excess carrier recombination time (low injection level approximation)

$$\begin{split} G_0 &= B n_0 p_0 \\ G_0 + R &= B n p \\ R &= \frac{\Delta n}{\tau} (e^- h^+ pairs) / cm^3 s \\ &= B \Delta n (n_0 + p_0) \\ \tau &\approx \frac{1}{B(n_0 + p_0)} \end{split}$$

Recombination: Non-equilibrium → equilibrium

Recombination rate = $B = B_r + B_{nr}$

 B_r = radiative

 B_{nr} = non-radiative

 $\mathsf{B}_{\mathsf{nr}} \propto \sigma_{\mathsf{traps}} \langle \mathsf{v}
angle$

Photon emission @ thermal equilibrium

GaAs

$$n_i = 1.8 \times 10^6 \, cm^{-3}$$

$$B_r = 10^{-10} \, \text{cm}^3 \, / \, \text{s}$$

$$G_{\scriptscriptstyle 0} = B_{\scriptscriptstyle r} n_{\scriptscriptstyle i}^2 = 324 \frac{Photons}{cm^3 s}$$

thickness of layer: $t = 2 \mu m = 2 \times 10^{-4} cm$ ($\alpha \sim 10^4 cm^{-1}$)

$$\varphi_v = \! \left(B_r n_i^2 \right) \! t = 6.48 \! \times \! 10^{-2} cm^{-2} s^{-1}$$

$$E_g=1.42\;eV$$

$$= 2.27 \times 10^{-19} J$$

$I = \varphi_{\nu} E_{q} = 1.5 \! \times \! 10^{-20} \, W/cm^{2}$

 $\Rightarrow \ \text{very low power}$

Internal Quantum Efficiency

Recombination = release of energy

radiating

$$\to h \upsilon$$

non-radiating ightarrow h u_{phonon} , Auger e^-

$$\eta_i = \frac{B_r}{B} = \frac{B_r}{B_r + B_{pr}}$$

$$\eta_{\text{i}} = \frac{\tau}{\tau_{\text{r}}} = \frac{\tau_{\text{nr}}}{\tau_{\text{r}} + \tau_{\text{nr}}}$$
 : fraction of non-equilibrium

carriers that recombine radiatively

R·V = injected (pairs)/s

$$\varphi = \text{ photon flux } = \frac{\eta_i RV}{A}$$

$$=\frac{\Delta n}{\tau_r}t$$

Notes

Interband recombination

GaAs:
$$\eta_i = 0.5$$

Si: $\eta_i = 10^{-5}$

GaAs:
$$\tau \simeq 50$$
 ns, $\eta_i = 0.5$, $\Delta n = 10^{17}$ cm⁻³
$$R = \Delta n / \tau = 10^{24} \text{ photons/cm}^3 / \text{s}$$

$$\begin{split} t &= 2 \; \mu \text{m} \\ \varphi_v &= \text{Rt} = 2 \times 10^{20} \; \text{cm}^{-2} \text{s}^{-1} \\ I &= \varphi_v \text{E}_g = \text{46 W/cm}^2 \end{split}$$

LED:
$$200 \mu m \times 100 \mu m$$
 area emitted power = $9 mW$

Spontaneous emission

Rate =
$$r_{sp}(\nu) = \frac{1}{\tau_r} \rho(\nu) f_e(\nu)$$

$$\rho(\nu) = \frac{(2m_r)^{3/2}}{\pi \hbar^2} (h\nu - E_g)^{1/2}$$

optical joint density of states

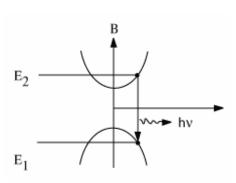
$$\frac{1}{m_r} = \frac{1}{m_v} + \frac{1}{m_c} \text{ (reduced mass)}$$

Emission condition

$$\begin{split} E_1 &= E_2 - h\nu \\ E_2 &= E_c + \frac{m_r}{m_c} (h\nu - E_g) \end{split}$$

$$\varphi = \frac{V}{A} \int\limits_0^\infty r_{\text{SP}}(\nu) d\nu$$

Notes



- (1) low injection ($\Delta n < n_0, p_0$) $\mathsf{R}\uparrow \to \Delta \mathsf{n}\uparrow \to (\mathsf{E}_{\mathsf{FC}}-\mathsf{E}_{\mathsf{FV}})\uparrow$
- (2) high injection ($\Delta n > n_0, p_0$)

Spectral density of emission rate

$$\mathbf{r}_{sp} = \mathbf{D}(\mathbf{h}\nu - \mathbf{E}_{g})^{1/2} \exp \left[\frac{-(\mathbf{h}\nu - \mathbf{E}_{g})}{\mathbf{K}_{B}\mathbf{T}} \right]$$

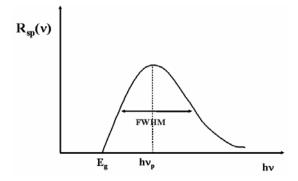
weak injection

$$D = \frac{\left(2m_r\right)^{3\!\!/2}}{\pi\hbar^2\tau_r} exp \left[\frac{\left(E_{FC} - E_{FV} - E_g\right)}{k_BT}\right]$$

same shape as thermal equilibrium:

$$r_{sp} = D_o (h\nu - E_g)^{1\!\!\!/2} \exp\!\left[\!\!\! \frac{-\! \left(h\nu - E_g\right)}{K_B T}\!\!\!\right] \label{eq:rsp}$$

Where
$$\frac{D}{D_o} \sim exp \bigg[\frac{\left(E_{FC} - E_{FV}\right)}{k_B T} \bigg]$$



 ν_P = Peak frequency

$$h\nu_{_P}=E_{_g}+\frac{1}{2}k_{_B}T$$

Notes

 $\boldsymbol{\lambda_{\text{g}}}$: bandgap wavelength

$$E_g$$
: bandgap energy
$$\lambda_g = \frac{1.24 \text{ eV} \cdot \mu m}{E_q}$$

FWHM

LED Devices

Internal photon flux

$$R = \frac{I/e}{V} = injection rate$$

I = current

e = charge/e

V = active volume

@ high injection levels

$$\Delta n > n_0, p_0$$

$$\Delta n = \frac{\left(\frac{I}{e}\right)\tau}{V}$$

Internal quantum efficiency

$$\eta_{\text{i}} \equiv \frac{\text{photon flux}}{\text{electron flux}}$$

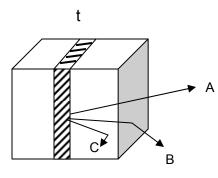
$$\phi = \eta_i \frac{1/A}{e}$$

External quantum efficiency

$$\eta_{\text{ext}} = \frac{\text{external photon flux}}{\text{electron flux}}$$

Notes

$$k_BT(300K) = 0.025 \text{ eV}$$



Surface emission

Notes

- 1. Absorption $(h\nu \simeq E_g)$ $\eta_1 = exp(-\alpha t)$
- 2. Reflection @ interface

$$\eta_2 = 1 - \frac{(n-1)^2}{(n+1)^2} = \frac{4n}{(n+1)^2}$$
= 0.68 for GaAs (n=3.6)

3. Total reflection

$$\eta_3 = 1 - \cos \theta_c \simeq \frac{1}{2n^2}$$
= 4% of GaAs

$$\begin{split} \eta_{\text{ext}} &= \eta_1 \cdot \eta_2 \cdot \eta_3 \cdot \eta_i \\ \text{output power} &= P_0 = h \nu \varphi_0 \end{split}$$

$P_{\text{out}} = \eta_{\text{ext}} \frac{h\nu}{e} I$

Power conversion wall plug efficiency

Responsivity

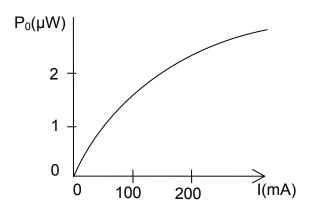
$$R \equiv \frac{P_0}{I} = V \eta_W = \eta_{\text{ext}} \frac{h \nu}{e}$$

$$R = \eta_{\text{ext}} \, \frac{1.24}{\lambda_{\text{0}}(\mu\text{m})} \frac{\text{W}}{\text{A}}$$

Typical:

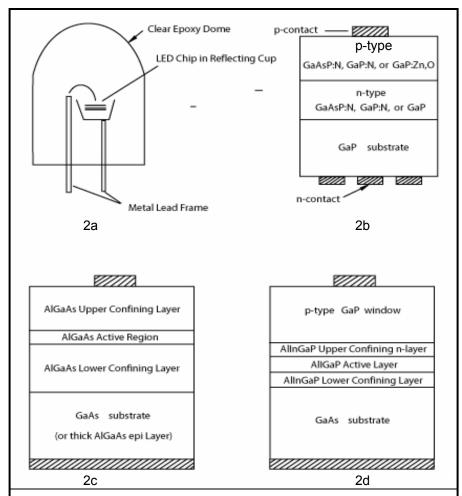
$$\eta_{ext}$$
 = 1.5% \Rightarrow R = 10-50 μ W/mA

Notes



Luminous performance (displays)

$$\frac{\text{lumens}}{\text{IV}} = \frac{P_0 \cdot \text{eye sensitivity}}{\text{IV}}$$



2. Typical LED device and chip configurations. (a) Cross-section of a LED lamp. The LED chip, typically 250 x 250 x 250 micrometers, is mounted in a reflecting cup formed in lead frame. Clear epoxy acts as a lens, as well as performing other functions. (b) A conventional homojunction LED chip can be made with GaAsP:N/GaP structures to emit at red and yellow wavelengths, and with GaP:N/GaP structures to emit at green wavelengths. (c) In a red-emitting AlGaAs double-heterostructure chip, the entire structure is grown by LPE and can be either n-type or p-type on top. (d) An AllnGaP double-heterostructure with a GaP window layer for red, yellow, or green emitters. The Al concentration in the p-type active region is adjusted to give the desired color.